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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: Bradley J. Howard

Filed: December 13, 2001

For: PROCESS FOR USING PHOTO-DEFINABLE LAYERS IN THE MANUFACTURE
OF SEMICONDUCTOR DEVICES AND RESULTING STRUCTURES OF SAME

Serial No.: 10/015,434

Group Art Unit: Unknown

Examiner: Unknown

Atty Dkt: 97-0008D1

Pursuant to 37 C.F.R. 1.8, I certify that this correspondence is being deposited with the U.S. Postal Service in a first class postage prepaid envelope addressed to: Assistant Commissioner for Patents, Washington, D.C. 20231 on the date below.

Date

Name

INFORMATION DISCLOSURE STATEMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

Pursuant to 37 C.F.R. §§ 1.56, 1.97, and 1.98, it is respectfully requested that this Information Disclosure Statement be entered and the documents listed on attached Form PTO-1449 be considered by the Examiner and made of record.

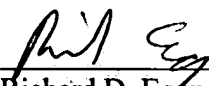
Copies of the listed documents required by 37 C.F.R. § 1.98(a)(2) are enclosed for the convenience of the Examiner.

If an appropriate check has not been enclosed, or if it is insufficient, the Commissioner is hereby authorized to deduct said fee from O'Keefe, Egan & Peterman Deposit Account No. 10-1205/MTIP:003D1.

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Applicant respectfully requests that the listed documents be made of record in the present case.

Respectfully submitted,


Richard D. Egan
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Enclosures

Form PTO-1449 (modified)

Atty. Docket No.
97-0008D1Serial No.
10/015,434

List of Patents and Publications for Applicant's

Applicant
Bradley J. Howard

INFORMATION DISCLOSURE STATEMENT

(Use several sheets if necessary)

Filing Date:
December 13, 2001Group:
UnknownU.S. Patent Documents
See Page 1Foreign Patent Documents
See Page 1Other Art
See Page 1

U.S. Patent Documents

Exam. Init.	Ref. Des.	Document Number	Date	Name	Class	Sub Class	Filing Date If App.
	A1	4,921,321	5/1/90	Weidman			
	A2	5,439,780	8/8/95	Joshi et al.			
	A3						

Foreign Patent Documents

Exam. Init.	Ref. Des.	Document Number	Date	Country	Class	Sub Class	Translation Yes/No
	B1						

Other Art (Including Author, Title, Date Pertinent Pages, Etc.)

Exam. Init.	Ref. Des.	Citation
	C1	Ajey M. Joshi et al., "Plasma Deposited Organosilicon Hydride Network Polymers as Versatile Resists for Entirely Dry Mid-Deep UV Photolithography," <i>SPIE</i> , Vol. 1925, pp. 709-720, January 1993.
	C2	O. Joubert et al., "Plasma polymerized - dry resist process for 0.25 μ m photolithography," <i>J. Vac. Sci. Technol. B</i> 12(6), pp. 3909-3913, Nov/Dec 1994.
	C3	O. Joubert et al., "Plasma Polymerized Organosilane Network Polymers; High Performance Resists for Positive and Negative Tone Deep UV Lithography," <i>SPIE</i> , Vol. 2195, pp. 358-371, May 1994.
	C4	T. W. Weidman et al., Applications of Plasma Polymerized Methylsilane as a Resist and Silicon Dioxide Precursor for 193 and 248 nm Lithography," <i>SPIE</i> , Vol. 2438, pp. 496-512, June 1995.
	C5	Timothy W. Weidman and Ajey M. Joshi, "New photodefinable glass etch masks for entirely dry photolithography: Plasma deposited organosilicon hydride polymers," <i>Appl. Phys. Lett.</i> 62(4), pp. 372-374, January 25, 1993

Examiner:

Date Considered:

EXAMINER: initial if reference considered, whether or not citation is in conformance with MPEP609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.